

### ABSTRACT

A retaining ring for use on a carrier head in a chemical mechanical polishing apparatus has a bottom surface, an inner surface and an outer surface, and a plurality of  
5 recesses on the bottom surface. Each recess can include an inner trailing surface and a slurry capture area. A channel can connect the slurry capture area to the inner surface. The inner trailing surface can be configured for fastening thereon an insert tool having a contact edge for abrasively contacting a polishing pad.

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